

# PATENT ABSTRACTS OF JAPAN

(11)Publication number : 2001-048931

(43)Date of publication of application : 20.02.2001

(51)Int.Cl.

C08F 20/10  
C08L 33/04  
G03F 7/039

(21)Application number : 11-223110

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(22)Date of filing : 05.08.1999

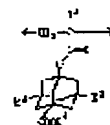
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## (54) POLYMER FOR PHOTORESIST AND RESIN COMPOSITION PHOTORESIST

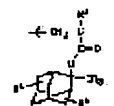
### (57)Abstract:

PROBLEM TO BE SOLVED: To obtain a polymer which has excellent transparency, excellent alkali solubility, excellent adhesivity and high etching resistance and is useful as a resin for photoresists by polymerizing the (meth)acrylate ester of a specific adamantanol derivative or the like.

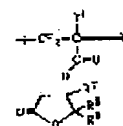
SOLUTION: This polymer comprises at least one kind of monomer units selected from monomer units of formula I (R1 is H or methyl; R2 and R3 are each H, OH or COOR4; R4 is t-butyl, 2-tetrahydrofuranyl, 2-tetrahydropyranyl or the like), formula II (R5 and R6 are each H, OH or O) and formula III (R7 to R9 are each H or methyl) [provided that when the monomer units of formula II or III (R5=R6=H) are contained, at least one kind of monomer units selected from formula I, formula II (at least one of R5 and R6 is OH or O) and formula IV (R10 and R11 are each H, OH or COOH; R12 is OH, O or COOH) are contained].



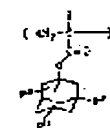
I



II



III



IV

### LEGAL STATUS

[Date of request for examination] 24.10.2000

[Date of sending the examiner's decision of 03.09.2002

rejection]

[Kind of final disposal of application other  
than the examiner's decision of rejection or  
application converted registration]

[Date of final disposal for application]

[Patent number] 3390702

[Date of registration] 17.01.2003

[Number of appeal against examiner's  
decision of rejection] 2002-19016

[Date of requesting appeal against  
examiner's decision of rejection] 30.09.2002

[Date of extinction of right]

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